

ABSTRACT OF THE DISCLOSURE

TITLE OF THE INVENTION

METHOD OF AND APPARATUS FOR PROCESSING PHOTORESIST,
METHOD OF EVALUATING PHOTORESIST FILM, AND PROCESSING
APPARATUS USING THE EVALUATION METHOD

5 A resist processing method includes setting a
substrate at a specific temperature, forming a resist
film on the substrate by applying a resist solution
onto the substrate while turning the substrate set at
the specific temperature, heating the substrate on
which the resist film has been formed, cooling the
substrate a specific temperature after the heating
process, wherein the thickness of the resist film on
10 the substrate is measured between the heating process
and the cooling process.

Fig. 1